

ISO 13424:2013-10 (E)

Surface chemical analysis - X-ray photoelectron spectroscopy - Reporting of results of thin-film analysis

Contents		Page
Foreword		iv
Introduction		v
1	Scope	1
2	Normative references	1
3	Terms and definitions	1
4	Abbreviated terms	1
5	Overview of thin-film analysis by XPS	1
5.1	Introduction	1
5.2	General XPS	3
5.3	Angle-resolved XPS	3
5.4	Peak-shape analysis	3
5.5	Variable photon energy XPS	3
5.6	XPS with sputter-depth profiling	3
6	Specimen handling	4
7	Instrument and operating conditions	4
7.1	Instrument calibration	4
7.2	Operating conditions	4
8	Reporting XPS method, experimental conditions, analysis parameters, and analytical results	5
8.1	XPS method for thin-film analysis	5
8.2	Experimental conditions	5
8.3	Analysis parameters	6
8.4	Examples of summary tables	7
8.5	Analytical Results	9
Annex A (informative)	General XPS	10
Annex B (informative)	Angle-resolved XPS	18
Annex C (informative)	Peak-shape analysis	24
Annex D (informative)	XPS with sputter-depth profiling	37
Bibliography		40